

QUERY CONTROL FORM			RTIS USE ONLY		
Application No.	<u>10/017,855</u>	Prepared by	<u>BRS</u>	Tracking Number	<u>05988030</u>
Examiner-GAU	<u>Maldonado, J - 2823</u>	Date	<u>8/31/04</u>	Week Date	<u>7/26/04</u>
		No. of queries	<u>1</u>	<u>IFW(E)</u>	

JACKET					
a. Serial No.	f. Foreign Priority	k. Print Claim(s)	<u>⑥ PTO-1449</u>		
b. Applicant(s)	g. Disclaimer	l. Print Fig.	q. PTOL-85b		
c. Continuing Data	h. Microfiche Appendix	m. Searched Column	r. Abstract		
d. PCT	i. Title	n. PTO-270/328	s. Sheets/Figs		
e. Domestic Priority	j. Claims Allowed	o. PTO-892	t. Other		

SPECIFICATION	MESSAGE <u>PTO-1449 : Please initial or strike through entries on PTO-1449 form dated 03-29-2002.</u> <u>(Copy attached for reference)</u>				
CLAIMS	<u>Thank You</u> initials <u>BRS</u>				
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Form PTO-1449
(MODIFIED)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.

39153/441 (G04061)

SERIAL NO.

10/017,855

APPLICANT

Philip A. Fisher et al.

INFORMATION DISCLOSURE CITATION

MAR 29 2002

FILING DATE

GROUP ART UNIT

(Use several sheets if necessary)

TECH. 12/14/2001

To be determined

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE IF APPROPRIATE
	A1	09/819.342		Shields et al.			03/28/01
	A2	09/819.343		Gabriel et al.			03/28/01
	A3	09/819.344		Okoroanyanwu et al.			03/28/01
	A4	09/819.552		Gabriel et al.			03/28/01
	A5	09/819.692		Okoroanyanwu et al			03/28/01
	A6	09/820.143		Okoroanyanwu et al.			03/28/01
	A7	6,107,172	08/22/00	Yang et al	438	585	
	A8	6,103,457	08/15/00	Gabriel	430	318	
	A9	5,965,461	10/12/99	Yang et al	438	717	
	A10	5,003,178	03/26/91	Livesay	250	492.300	

FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

A11	Livesay, W. R., "Large-area electron-beam source," Journal of Vacuum Science & Technology B, Vol. 11, No. 6, Nov./Dec. 1993, pp. 2304-2308. American Vacuum Society
A12	Yank, J. J. et al, "Electron Beam Processing for Spin-on Polymers and its Applications to Back-End-of-Line (BEOL) Integration," Materials Research Society Symposium Proceedings, Vol. 511, 1998, pp. 49-55. Materials Research Society
A13	Ross et al, "Plasma Etch Characteristics of Electron Beam Processed Photoresist," The Society of Photo-Optical Instrumentation Engineers, Vol. 2438, 1995, pp. 803-816. SPIE- The International Society for Optical Engineering
A14	Grün, Von A.E., "Lumineszenz-photometrische Mesungen der Energieabsorption im Strahlungsfeld von Elektronenquellen Eindimensionaler Fall in Luft," Zeitschrift für Naturforschung, Vol. 12a, 1957, pp. 89-95. Publisher: Zeitschrift für Naturforschung: full English Translation attached (11 pgs.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.